

METHOD AND APPARATUS TO EASILY MEASURE RETICLE BLIND POSITIONING WITH AN EXPOSURE APPARATUS

Abstract of the Disclosure

A method, exposure apparatus, and printed wafer such that a design is printed within a peripheral portion of the wafer. The peripheral portion of the wafer is between an outer boundary of an active portion of the wafer and an outer boundary of the wafer. The exposure apparatus comprises a lens, a reticle that includes a pattern, and a reticle blind. The reticle blind blocks a first portion of light that is passed through the exposure apparatus. A transparent portion of the reticle transmits a remaining portion of the light. The lens focuses the remaining portion of the light onto the wafer such that an image of a portion of the pattern is printed as the design within the peripheral portion of the wafer. The printed design is a function of where the reticle blind is positioned relative to the pattern.

Figures